Wafer Cleaning Procedure

1. Pre-Cleaning Instructions
   1.1. Double glove before all cleaning processes.
   1.2. Capture all solvent waste into the solvent waste jug in the solvent hood.
   1.3. Refill an acetone and isopropanol (IPA) squirt bottle prior to cleaning.

2. Tweezer Cleaning
   2.1. Rinse the tweezer with de-ionized (DI) water over the sink.
   2.2. Inspect tweezer for foreign material.
   2.3. Remove any foreign material with acetone and a swab or wipe.
   2.4. Rinse the tweezer with acetone into the solvent waste jug.
   2.5. Rinse the tweezer with IPA into the solvent waste jug.
   2.6. Place a 4x4 polyester wipe on top of a 4x4 cellulose wipe on the solvent hood bench.
   2.7. Blow dry the tweezers with nitrogen, using the polyester wipe to absorb any IPA coming off the tweezers.

3. Wafer Cleaning
   3.1. Place a 4x4 polyester wipe on top of a 4x4 cellulose wipe in the solvent hood.
   3.2. Using a wafer tweezer, pickup the wafer on the wafer flat.
   3.3. Rinse the entire wafer with de-ionized (DI) water over the sink.
   3.4. Rinse the entire wafer with acetone into the solvent waste jug.
   3.5. Rinse the entire wafer with IPA into the solvent waste jug.
   3.6. Blow dry the wafer with nitrogen, starting from the top of wafer and going down, using the polyester wipe to absorb any IPA coming off the wafer.